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	Application No.	Applicant(s)	
Notice of Allowability	10/754,320	WONG, ROBERT C.	
	Examiner	Art Unit	C.
	A delle mb	2040	
	Andy Huynh	2818	
The MAILING DATE of this communication app All claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.31	S (OR REMAINS) CLOSED in) or other appropriate communication is second RIGHTS. This application is second MPEP 1308.	n this application. If not includ unication will be mailed in due	ed course. THIS
1. $igotimes$ This communication is responsive to $the Amendment date$	ed 04/18/05.		
2. The allowed claim(s) is/are <u>1-7 and 9-23.</u>			
3. $igotimes$ The drawings filed on <u>08 January 2004</u> are accepted by the	ne Examiner.		
4. Acknowledgment is made of a claim for foreign priority u a) All b) Some* c) None of the: 1. Certified copies of the priority documents hav 2. Certified copies of the priority documents hav 3. Copies of the certified copies of the priority do International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDON! THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	re been received. The been received in Application ocuments have been received. The been received in the been rece	on Nod in this national stage applicated in this national stage applicated in the relationship is a reply complying with the re	quirements
 A SUBSTITUTE OATH OR DECLARATION must be subn INFORMAL PATENT APPLICATION (PTO-152) which give 			NOTICE OF
6. \square CORRECTED DRAWINGS (as "replacement sheets") mu	ist be submitted.		•
(a) Including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached			
1) 🗌 hereto or 2) 🗍 to Paper No./Mail Date			
(b) including changes required by the attached Examiner Paper No./Mail Date	's Amendment / Comment o	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR each sheet. Replacement sheet(s) should be labeled as such in	1.84(c)) should be written on t the header according to 37 CF	he drawings in the front (not the FR 1.121(d).	e back) of
 DEPOSIT OF and/or INFORMATION about the deposit attached Examiner's comment regarding REQUIREMENT 	OSIT OF BIOLOGICAL MATE FOR THE DEPOSIT OF BIO	ERIAL must be submitted. DLOGICAL MATERIAL.	Note the
Attachment(s)	E Nation of la	formal Patent Application (PT	·O_152\
 Notice of References Cited (PTO-892) Notice of Draftperson's Patent Drawing Review (PTO-948) 		ummary (PTO-413),	0-102)
	Paper No.,	/Mail Date	
3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/ Paper No./Mail Date <u>04/18/05</u>		Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	8. ⊠ Examiner's 9. ☐ Other	Statement of Reasons for All	Ovvarice
of Biological Material		Ly Vreyol dy Hughl tent Examina u 2818	
U.S. Patent and Trademark Office	70.	- \ -010	

DETAILED ACTION

In the Amendment dated April 18, 2005, claims 8 and 24 are canceled without prejudice and claims 1, 6, 14 and 15 are amended is acknowledged. Accordingly, claims 1-7 and 9-23 remain pending in the present application.

Allowable Subject Matter

Claims 1-7 and 9-23 are allowed.

The following is an examiner's statement of reason for allowance:

Claims 1-7 and 9-13 are allowable over the prior art of record because the prior art of record does not teach or render obvious a selective silicon-on-insulator (SOI) structure comprises a DC node diffusion region is located within bulk silicon without oxide underneath thereby the DC node diffusion region, and in combination with all other features as recited in independent claim 1.

Claim 14 is allowable over the prior art of record because the prior art of record does not teach or render obvious a integrated circuit comprises a DC node diffusion region is located within bulk silicon without oxide underneath thereby the DC node diffusion region, and in combination with all other features.

Claims 15-23 are allowable over the prior art of record because the prior art of record does not teach or render obvious a semiconductor substrate comprises a DC node diffusion region is located within bulk silicon without oxide underneath thereby the DC node diffusion region, and in combination with all other features as recited in independent claim 15.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

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fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance".

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Andy Huynh whose telephone number is (571) 272-1781. The examiner can normally be reached on Monday-Friday 8:30am-5:00pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on (571) 272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 872-9306 for regular communications and (703) 872-9306 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Ah

04/21/05

Andy Huynh

andy Muy D

Patent Examiner